



אוניברסיטת בן-גוריון בנגב  
Ben-Gurion University  
of the Negev

Nano-Fabrication  
Center

# HMx

## SUSS MicroTech



### Description

The HMxSquare is designed to address the needs of the semiconductor industry regarding to automation of substrate wet cleaning, photoresist development and chrome wet etching in photomask applications as well as in optoelectronics, OLED, and special semiconductor back-end (MEMS) applications.

HMxSquare offers programmed development, etching and cleaning functionalities. Active liquids are pneumatically transferred to spray nozzles and sprayed on rotating substrates. In the end of process the substrate is washed and centrifugally dried.

### Specifications / Capabilities

Wet cleaning processes: Acid cleaning (Piranha),  
1 MHz megasonic cleaning by DI  
Ammonia

Development process: with developer 400K

Etching process: Chrome etchant

Substrate sizes: 2 inch to 5 inch

### Link

<http://www.suss.com/en.html>

<http://www.suss.com/en/products-solutions/products/photomask-equipment/hmx-series/configurations.html>